

AMENDMENTS TO THE CLAIMS

Please amend the claims as set forth below in marked-up form.

1. (Currently Amended) A thin-film deposition device comprising:
a vacuum chamber;
a substrate holder provided in the vacuum chamber; and
at least one tubular gas supply end that supplies gas towards a substrate mounting-face
on the substrate holder,

wherein the gas supply end includes therein barriers that control the gas flow in the gas
supply end and that are disposed at predetermined intervals toward a gas supply port of the gas
supply end, each of the barriers having a plurality of apertures,

wherein the barriers that are disposed closer to the gas supply port have a larger number
of apertures each having smaller opening spaces than the barriers disposed further from the gas
supply port.

2. (Canceled)

3. (Original) The thin-film deposition device according to Claim 1, wherein said at least
one tubular gas supply end comprises a plurality of gas supply ends.

4. (Original) The thin-film deposition device according to Claim 1, wherein the gas
supply end is connected with a plurality of gas supply tubes that introduce gas into the gas
supply end.

5. (Original) The thin-film deposition device according to Claim 1, wherein the gas
supply end has a structure such that gas is supplied in a collimated fashion to a long rectangular
area on the substrate mounting-face across the width thereof.

6. (Original) The thin-film deposition device according to Claim 5, wherein the substrate holder includes a sliding mechanism that moves the substrate mounting-face parallel to the short axis of the long rectangular area to which the gas is supplied.

7. (Original) The thin-film deposition device according to Claim 1, wherein the gas supply end has a structure such that gas is supplied to the entire surface of a substrate mounted on the substrate mounting-face.